
Problem Statement

- **Reflections from interconnect will limit VLSI system performance**
- **This is caused by :**
 - 1) Inductive Package Interconnect**
 - 2) Faster Risetimes in Off-chip Driver Circuitry**

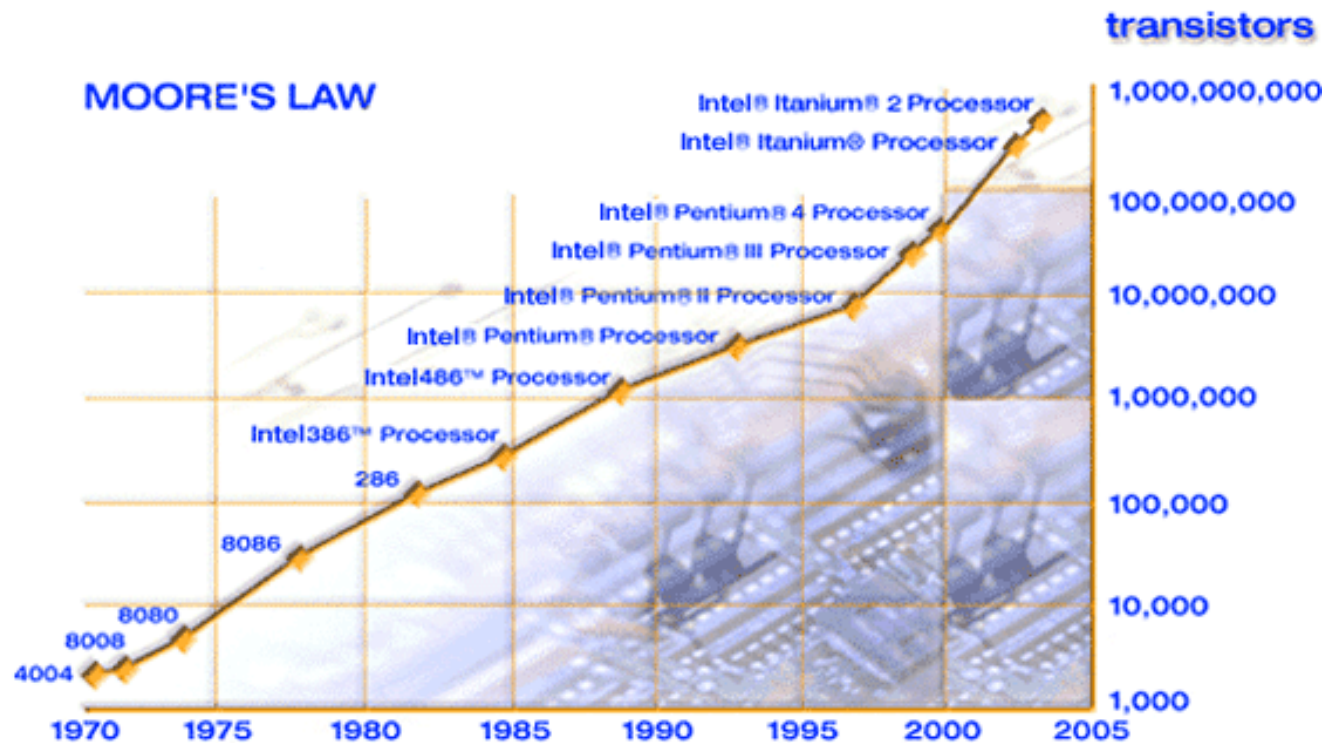
Agenda

1) Inductive Package Interconnect

2) Proposed Solution

3) Experimental Results

Why is packaging limiting performance?



Transistor Technology is Outpacing Package Technology

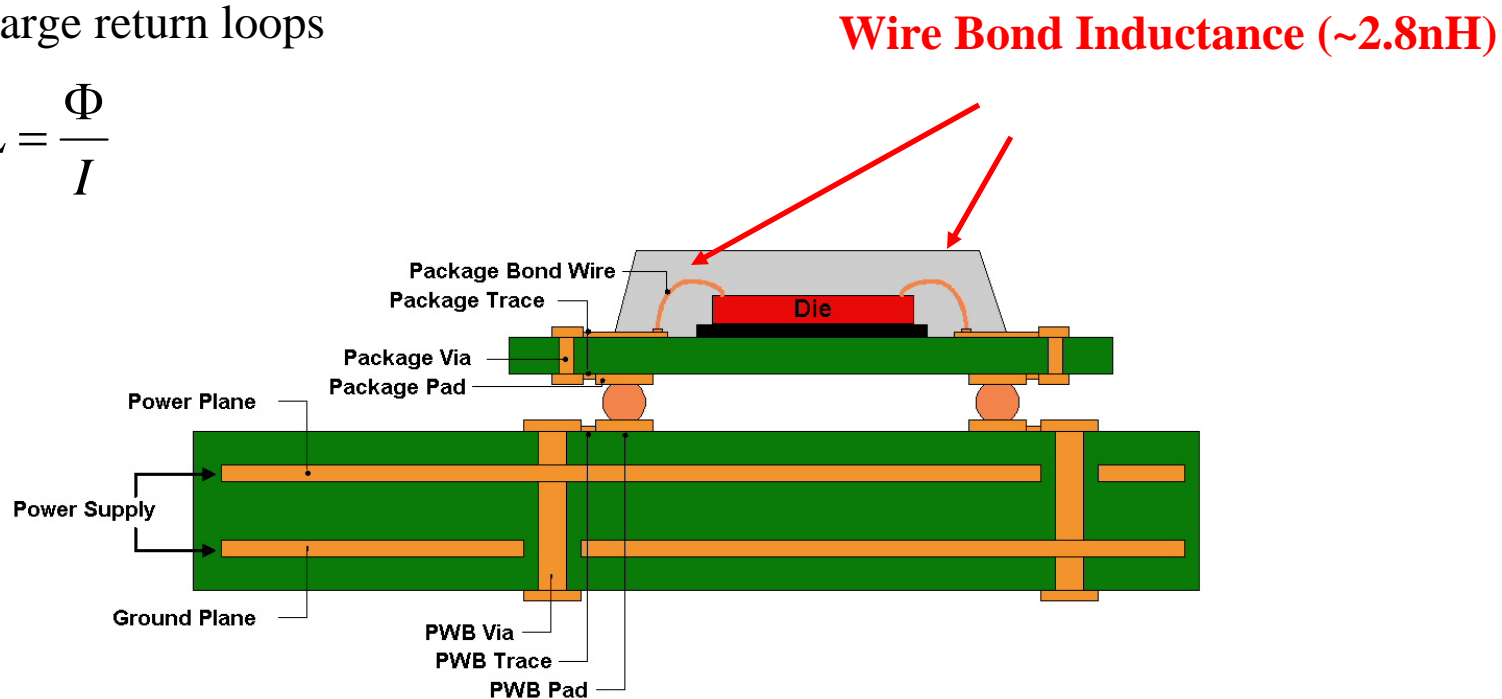
Why is packaging limiting performance?

- Package Interconnect Looks Inductive

- Long interconnect paths

- Large return loops

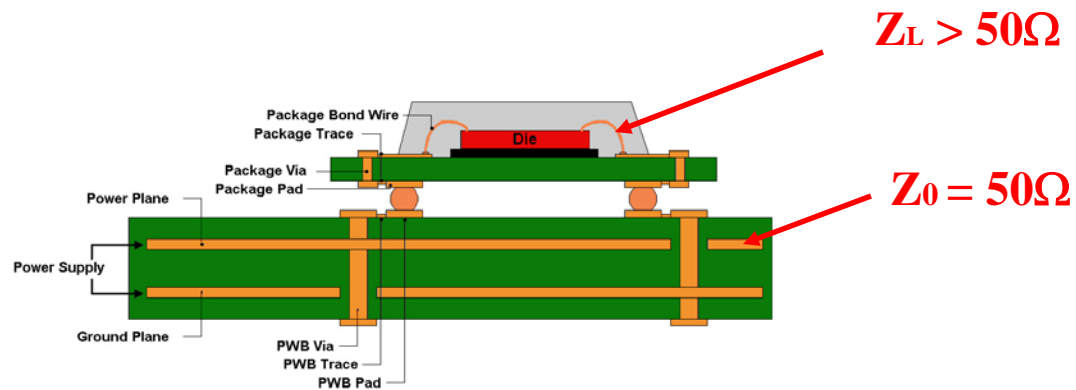
- $L = \frac{\Phi}{I}$



Why is packaging limiting performance?

- Inductive Interconnect Leads to Reflections

- Interconnect is not matched to system
- Reflections occur due to interconnect

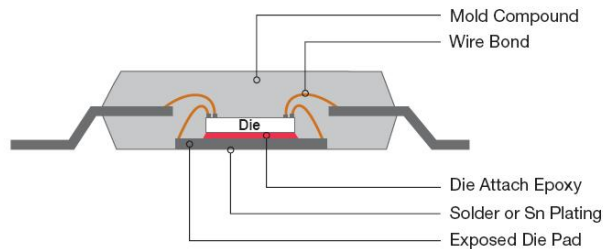


$$\Gamma = \frac{Z_L - Z_0}{Z_L + Z_0}$$

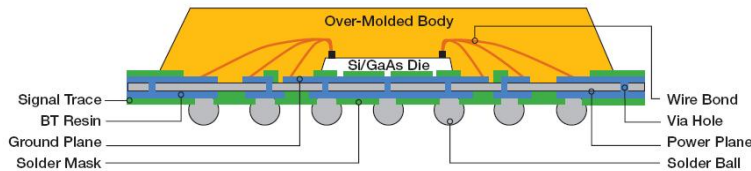
Why is packaging limiting performance?

- **Aggressive Package Design Helps, but is expensive...**

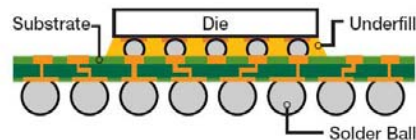
- **95% of VLSI design-starts are wire bonded**
- **Goal: Extend the life of wire bonded packages**



QFP – Wire Bond : 4.5nH → \$0.22 / pin



BGA – Wire Bond : 3.7nH → \$0.34 / pin ***



BGA – Flip-Chip : 1.2nH → \$0.63 / pin

Why Now?

Cost

- Historically, the transistor delay has dominated performance.
- Inexpensive packaging has met the electrical performance needs.

Faster Risetimes

- As transistors shrink, faster risetimes can be created.
- Everything in the package becomes a transmission line.

Impedance Matching

- The impedance of the package is not matched to the system.
- This leads to reflections from the inductive wire bond in the package

Current Solution to Reflections

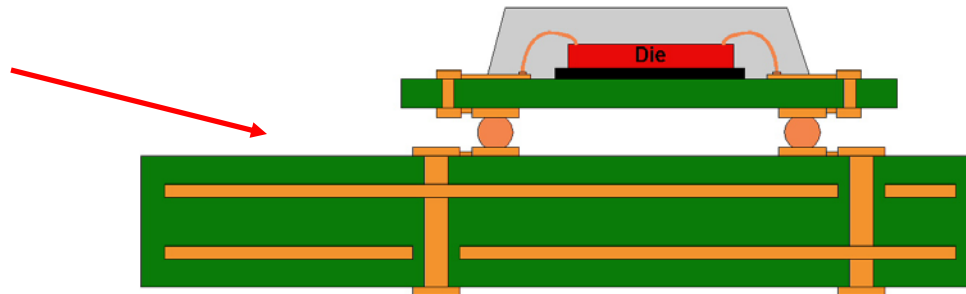
- **Live with the Signal Path Reflections**

1) **Run the signals slow enough so that reflections are small**

$$\Gamma = \frac{Z_L - Z_0}{Z_L + Z_0} < 10\%$$

2) **Terminate Signals on the Mother board so that reflections are absorbed**

On Mother Board Termination



Current Solution to Reflections

- **Limitations of Approach**

- 1) **Run the signals slow enough so that reflections are small**

- **Limits System Performance**

- 2) **Terminate Signals on the Mother board so that reflections are absorbed**

- **This only eliminates primary reflections, the second still exists**

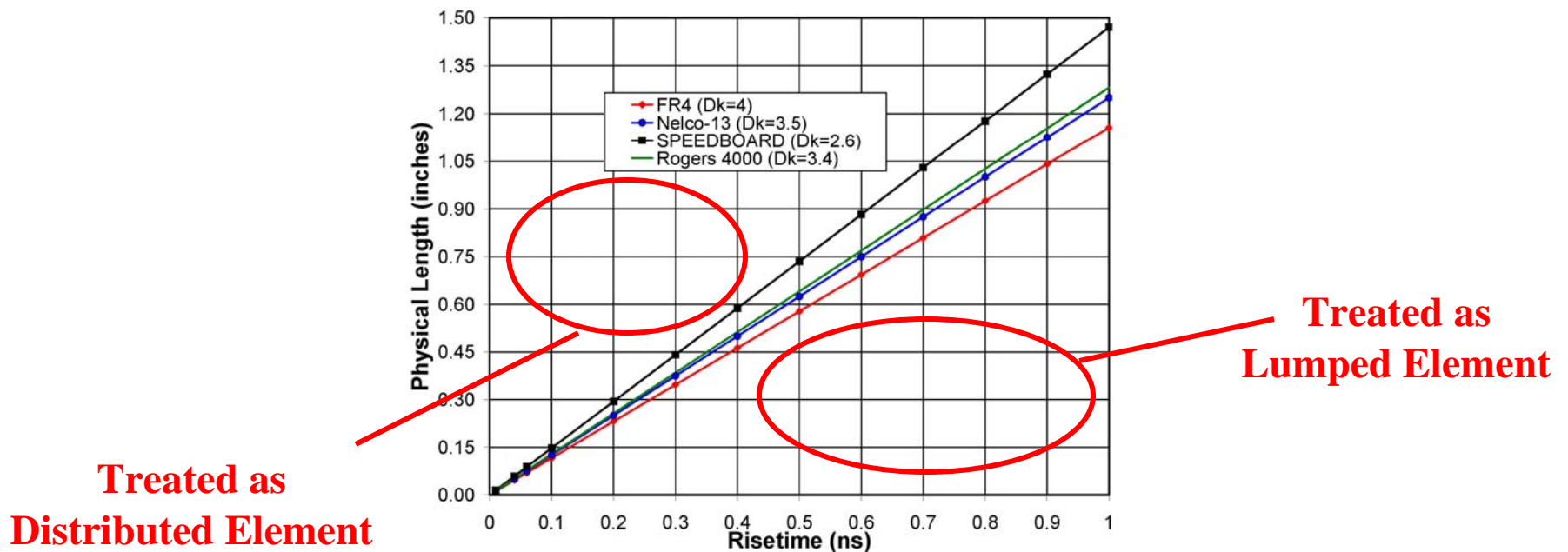
Proposed Solutions – Impedance Compensation

- **Add Capacitance Near Bond Wire to Reduce Impedance**
 - Adding additional capacitance lowers the wire bond impedance
 - Impedance can be matched to system, reducing reflections

$$Z_{WireBond} = \sqrt{\frac{L_{WireBond}}{C_{WireBond}}} \longleftarrow \text{Add Capacitance to lower } Z$$

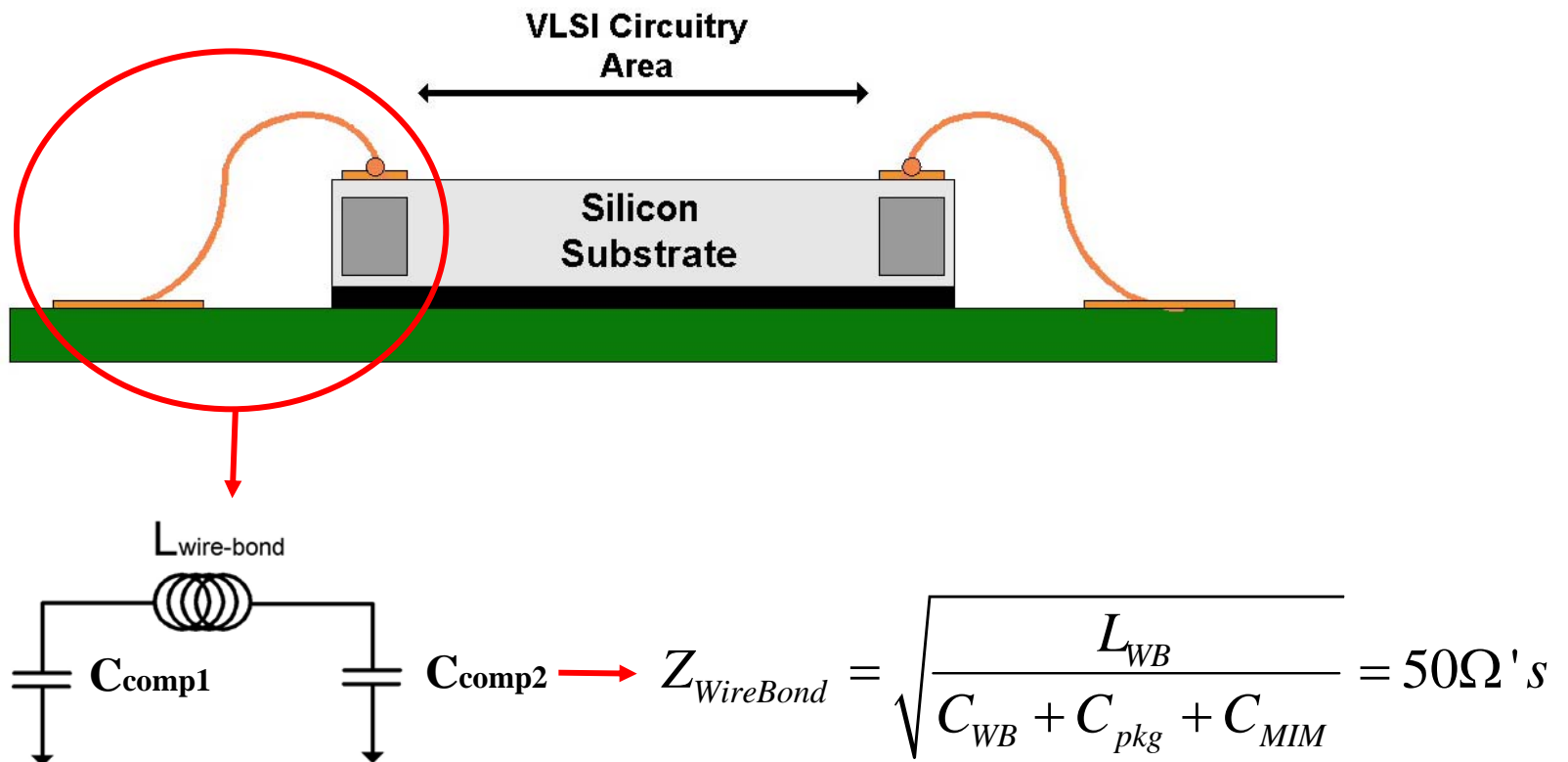
Proposed Solutions – Impedance Compensation

- If the capacitance is close to the wire bond, it will alter its impedance
- Electrical lengths less than 20% of risetime are treated as lumped elements
- For modern dielectrics, anything within 0.15” of wire bond is lumped



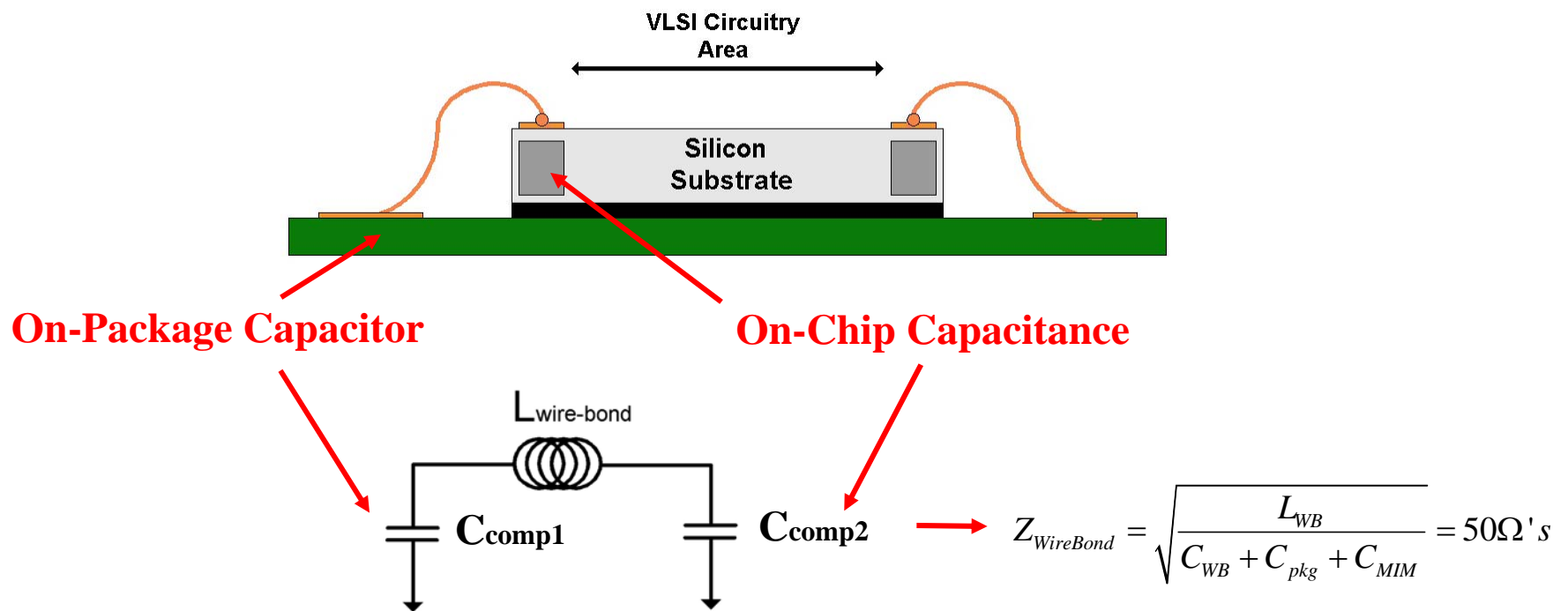
Proposed Solutions – Impedance Compensation

- Capacitance on the IC or Package is close enough to alter impedance



Static Compensator

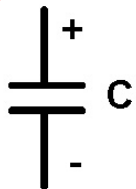
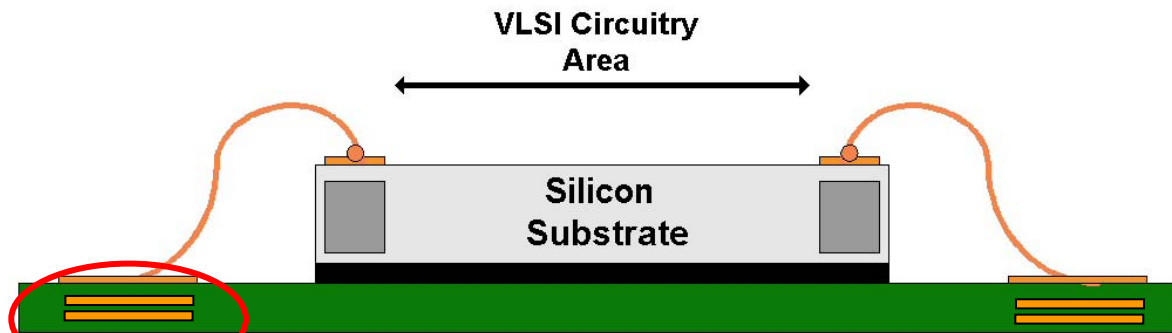
- Capacitor values chosen prior to fabrication
- Equal amounts of capacitance are used on-chip and on-package



Static Compensator

- On-Package Capacitors

- Embedded capacitor construction is used
- No components are needed, reducing package cost
- Capacitance values needed can be implemented using this construction

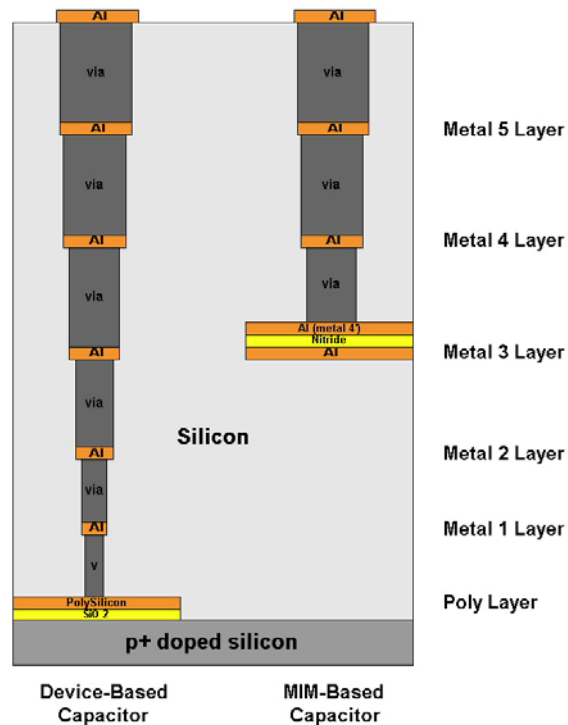


- Modern Packages can achieve plane-to-plane separations of $t=0.002''$
- This translates to $0.64\text{pF}/\text{mm}^2$

Static Compensator

- On-Chip Capacitors

- Device and MIM capacitors are evaluated
- Targeting area beneath wire bond pad, which is typically unused



0.1um BPTM Process

- Device-Based Capacitor : $13 \text{ fF}/\mu\text{m}^2$
- MIM-Based Capacitor : $1.1 \text{ fF}/\mu\text{m}^2$

Static Compensator

- **Inductor Modeling**

- Typical VLSI wire bond lengths range from 1mm to 5mm
- Electrical parameter extraction is used to find **L** and **C** or wire bond

<u>Length</u>	<u>L</u>	<u>C</u>	<u>Z₀</u>
1mm	0.569nH	26fF	148Ω
2mm	1.138nH	52fF	148Ω
3mm	1.707nH	78fF	148Ω
4mm	2.276nH	104fF	148Ω
5mm	2.845nH	130fF	148Ω

Static Compensator

- **On-Package Capacitor Sizing**

- Capacitor values are found to match wire bond to **50Ω**
- Area is evaluated for feasibility

<u>Length</u>	<u>C_{comp1}</u>		<u>C_{comp2}</u>		
<u>L</u>	<u>C</u>	<u>Area</u>	<u>C</u>	<u>Area_{MIM}</u>	<u>Area_{Device}</u>
1mm	102 fF	388 μm^2	102 fF	10 μm^2	2.7 μm^2
2mm	208 fF	554 μm^2	208 fF	14 μm^2	3.9 μm^2
3mm	325 fF	692 μm^2	325 fF	18 μm^2	4.9 μm^2
4mm	450 fF	815 μm^2	450 fF	21 μm^2	5.8 μm^2
5mm	575 fF	921 μm^2	575 fF	24 μm^2	6.5 μm^2

Experimental Results: Static Compensator

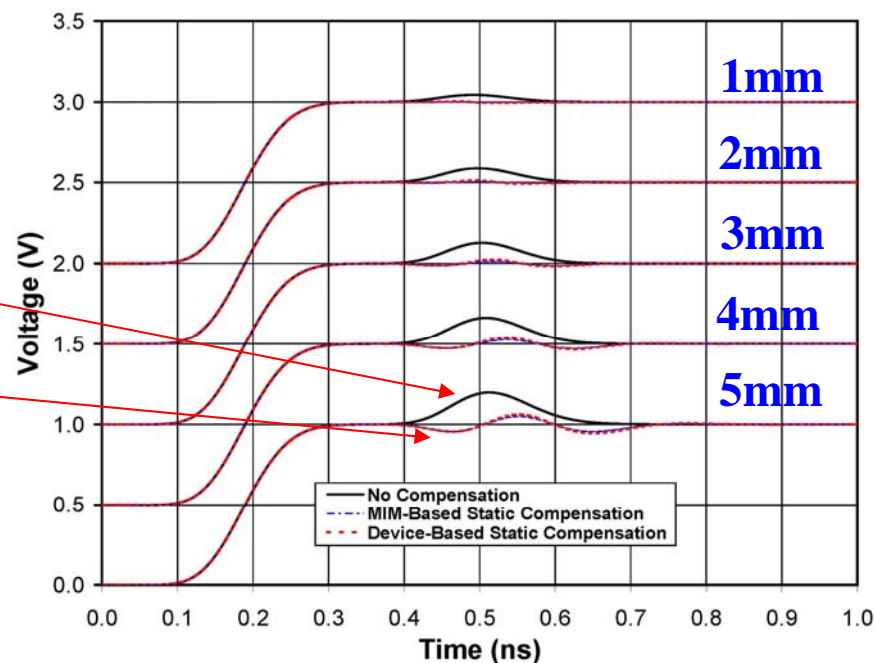
- Time Domain Analysis (TDR)

$Length_{wb}$	$\Gamma_{No-Comp}$	$\Gamma_{MIM-Comp}$	$\Gamma_{Device-Comp}$
1 mm	4.5%	0.05%	0.5%
2 mm	8.7%	0.4%	1.2%
3 mm	12.7%	1.3%	2.4%
4 mm	16.4%	2.7%	4.1%
5 mm	19.8%	4.8%	6.0%

Worst Case : 5mm

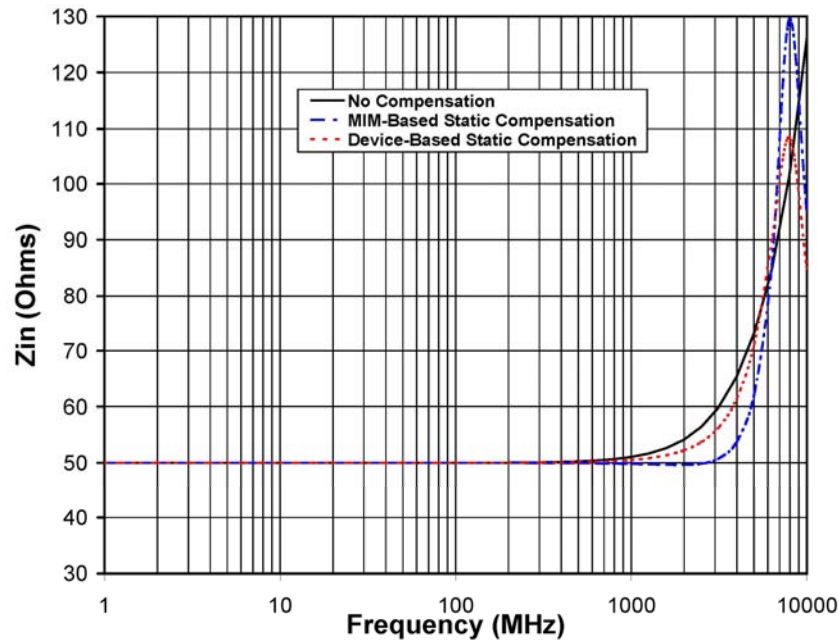
No Static Capacitance = 19.8%

w/ Static Capacitance = 4.8%



Experimental Results: Static Compensator

• Frequency Domain Analysis (Z_{in})



3mm

Worst Case : 5mm

$f_{\pm 10\%}$ No Static Capacitance = 1.9 GHz

$f_{\pm 10\%}$ w/ Static Capacitance = 3.0 GHz

$Length_{wb}$	$f_{No-Comp}$	$f_{MIM-Comp}$	$f_{Device-Comp}$
1 mm	9.3 GHz	14 GHz	12 GHz
2 mm	4.7 GHz	7.1 GHz	5.7 GHz
3 mm	3.1 GHz	4.8 GHz	3.8 GHz
4 mm	2.4 GHz	3.7 GHz	2.9 GHz
5 mm	1.9 GHz	3.0 GHz	2.5 GHz

Static Compensator

- **Limitations of Approach**

- **Process/Design variation in wire bonds and capacitors lead to error**
- **Each wire bond must be evaluated for compensation requirements**

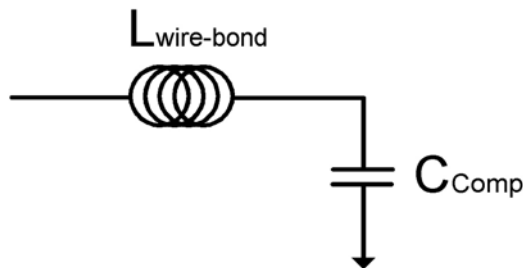
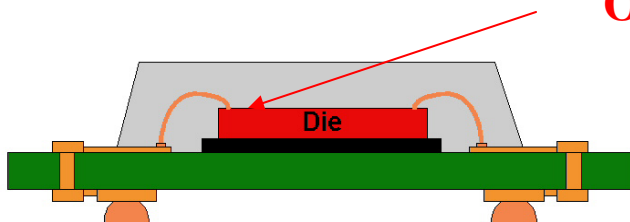
- **Possible Enhancement**

- **Altering compensation capacitance after fabrication**
- **i.e., *Dynamic Compensator***

Dynamic Compensator

- Programmable capacitance is placed on-chip
 - On-chip capacitance is close enough to alter wire bond impedance
 - Active circuitry on-chip can switch in different amounts of capacitance

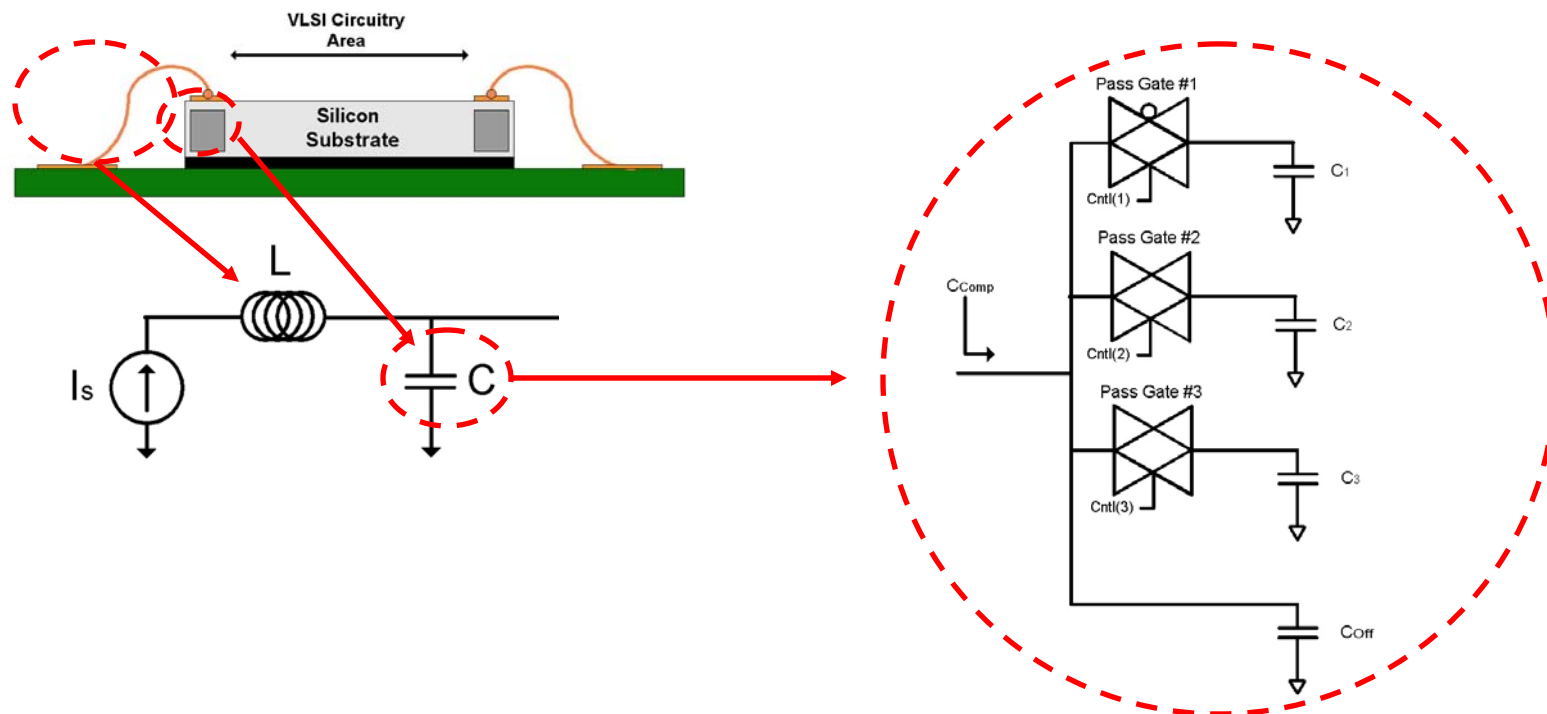
On-Chip Programmable Compensation



$$Z_{\text{WireBond}} = \sqrt{\frac{L_{\text{WB}}}{C_{\text{WB}} + C_{\text{Comp}}}} = 50\Omega's$$

Dynamic Compensator

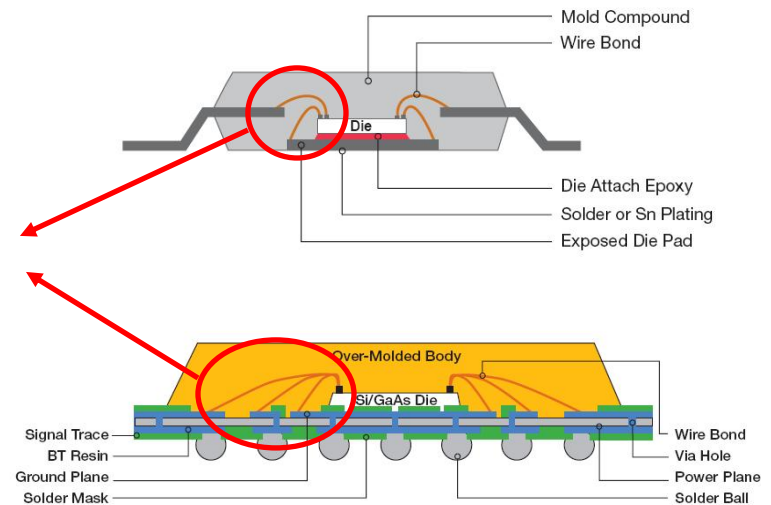
- **Pass Gates are used to switch in on-chip capacitors**
 - **Pass gates connect on-chip capacitance to the wire bond inductance**
 - **Pass gates have control signals which can be programmed after fabrication**



Dynamic Compensator

- **On-Chip circuitry is independent of package**
 - Compensation works across multiple package technologies
 - This decouples IC and Package design

Only IC technology is used for compensation



Dynamic Compensator

- **On-Chip capacitor sizing**

- The on-chip capacitance performs the compensation to **50Ω**
- The circuit must cover the entire range of wire bond inductances
- The diffusion capacitance of the pass gates must be included in the analysis

<u>Length</u>	<u>C_{comp}</u>
<u>L</u>	<u>C</u>
1mm	202 fF
2mm	403 fF
3mm	605 fF
4mm	806 fF
5mm	1008 fF

$$200 \text{ fF} \leq C_{\text{comp}} \leq 1010 \text{ fF}$$

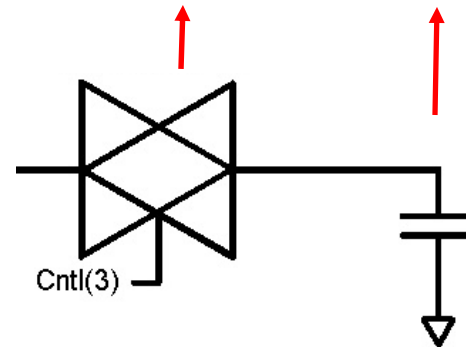
Dynamic Compensator

- **Compensator Design**

- The on-chip capacitance performs the compensation to **50Ω**
- The diffusion capacitance of the pass gates must be included in the analysis

<u>Length</u>	<u>C_{comp}</u>
<u>L</u>	<u>C</u>
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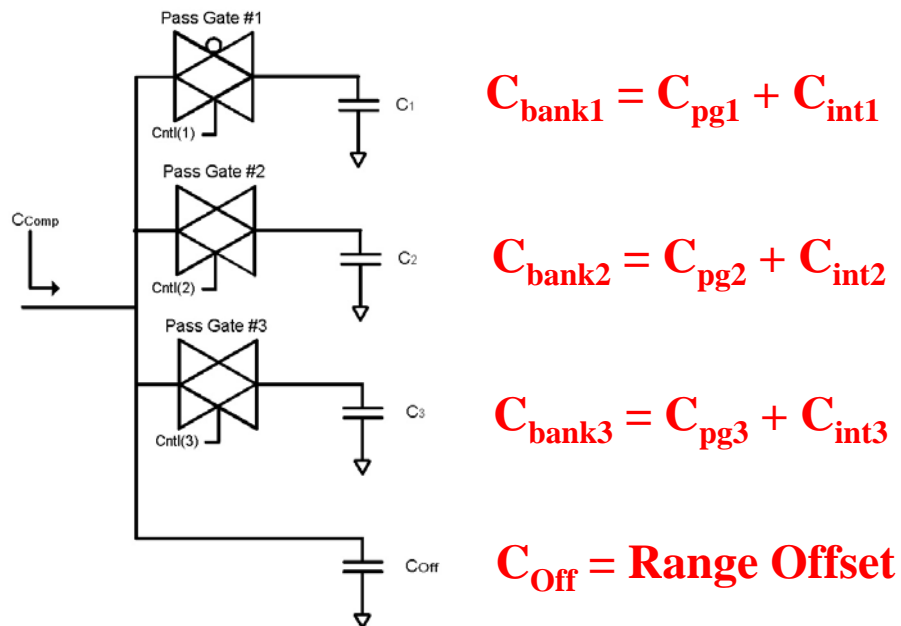
$$C_{\text{bank}} = \frac{1}{3}(C_{\text{bank}}) + \frac{2}{3}(C_{\text{bank}})$$



Dynamic Compensator

- **Capacitance Design**

- **Pass Gates are sized to drive the on-chip capacitance**
- **Each *bank* of capacitance includes the pass gates**



Dynamic Compensator

- **Capacitance Design**

- **Again, both MIM and Device-based capacitors are evaluated for area**

	MIM-Based	Device-Based
Component	Area (W × L)	Area (W × L)
Pass Gate #1	32.4 μm × 0.1 μm	32.4 μm × 0.1 μm
Pass Gate #2	62.5 μm × 0.1 μm	62.5 μm × 0.1 μm
Pass Gate #3	129.6 μm × 0.1 μm	129.6 μm × 0.1 μm
C_{off}	8.5 μm × 8.5 μm	2.5 μm × 2.5 μm
C_1	11 μm × 11 μm	3.3 μm × 3.3 μm
C_2	15.5 μm × 15.5 μm	4.6 μm × 4.6 μm
C_3	22 μm × 22 μm	6.6 μm × 6.6 μm
Total	65 μm × 65 μm	25 μm × 25 μm

Experimental Results: Dynamic Compensator

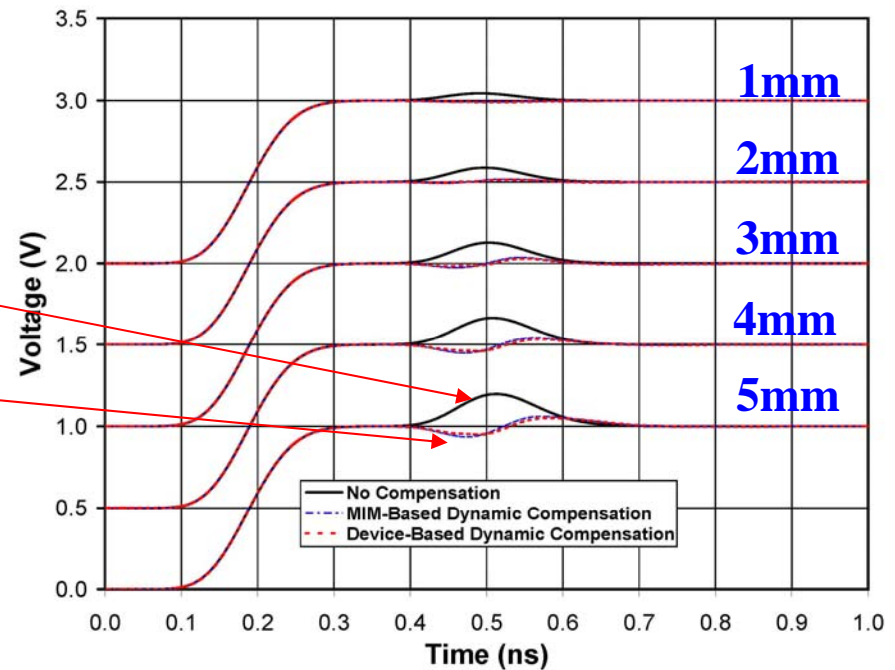
- Time Domain Analysis (TDR)

$Length_{wb}$	$\Gamma_{No-Comp}$	$\Gamma_{MIM-Comp}$	$\Gamma_{Device-Comp}$	Setting
1 mm	4.5%	1.0%	1.0%	001
2 mm	8.7%	1.8%	1.3%	011
3 mm	12.7%	3.6%	3.0%	100
4 mm	16.4%	4.3%	3.3%	110
5 mm	19.8%	6.0%	5.0%	111

Worst Case : 5mm

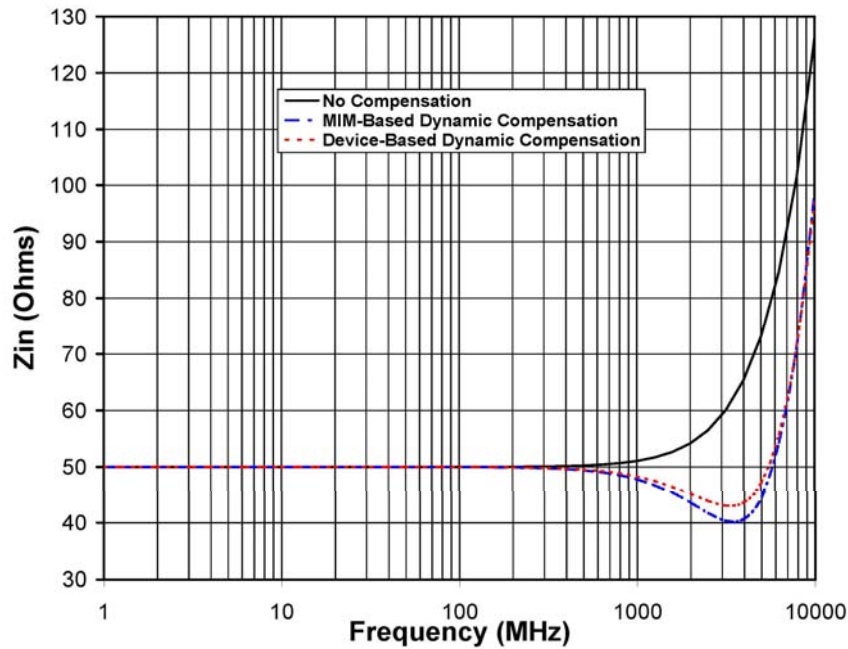
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Experimental Results: Dynamic Compensator

- Frequency Domain Analysis (Z_{in})



3mm

Worst Case : 5mm

$f_{\pm 10\%}$ No Dynamic Capacitance = 1.9 GHz

$f_{\pm 10\%}$ w/ Dynamic Capacitance = 4.1 GHz

$Length_{wb}$	$f_{No-Comp}$	$f_{MIM-Comp}$	$f_{Device-Comp}$
1 mm	9.3 GHz	20 GHz	20 GHz
2 mm	4.7 GHz	10.1 GHz	10 GHz
3 mm	3.1 GHz	6.8 GHz	6.7 GHz
4 mm	2.4 GHz	5.2 GHz	5.1 GHz
5 mm	1.9 GHz	4.2 GHz	4.1 GHz

Summary

- **Inductive Package Interconnect causes reflections which limits system performance**
- **The move toward Advanced Packaging is Resisted due to Cost**
- **Adding On-Chip & On-Package capacitors does **not** add cost**
- **A Static and Dynamic Compensation Approach can match the package interconnect impedance to the system**

Questions?